



U.S. PATENT & TRADEMARK OFFICE

In re application of: MARAHTANOV et al Serial No.: 10/808,795 Filed: March 24, 2004 Title: PLASMA PROCESSING SYSTEM CONTROL	Group Art Unit: 2821 Examiner: UNASSIGEND Docket: P1220/LMRX-P030 Confirmation No.: 6020 CERTIFICATE OF MAILING I hereby certify that this correspondence is being deposited with the US Postal Service as First Class Mail in a postage-paid envelope addressed to the Assistant Commissioner for Patents, Washington, DC 20231 on December 6, 2004. Signed: _____/Hanh H. Bui/ Hanh H. Bui
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INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

The references listed in the attached PTO Form 1449 may be material to the patentability of the above-identified patent application. Applicants submit the list of these references in compliance with their duty of disclosure pursuant to 37 CFR §§ 1.56 and 1.97. The Examiner is requested to make these references of official record in this application.

This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This IDS is submitted before the mailing of a first office action on the merits.

If the Commissioner determines that additional fees are required to process this Information Disclosure Statement, the Commissioner is hereby authorized to charge such fees to Deposit Account 50-2284 (Order No. LMRX-P030).

Respectfully submitted,
/Joseph A. Nguyen/
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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INFORMATION DISCLOSURE STATEMENT

US PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Case
		US-5933314	1999-08-03	Lambson et al.	

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Applicant	Reference to Related Case	T

OTHER DOCUMENTS

Examiner Initials	Cite No.		T
		Kawamura et al., "Ion energy distributions in RF sheaths; review, analysis and simulation", 1999, Plasma Sources Science Technology 8, R45-R64.	
		Lieberman et al., "Principles of Plasma Discharges and Materials Processing", 1994, New York, John Wiley and Sons, Inc..	

Examiner Signature		Date Considered	
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